

Registration

Online

<http://beams-and-more.ims-chips.de>

Deadline for registration

October 25th, 2019

Participation fee (includes lunch + dinner)

185,- EUR taxfree seminar

Speakers free.

You will receive a confirmation of registration and invoice.

Cancellation policy

In case of cancellation after expiration of the deadline 75% of the fee will be charged.

It is possible to send a substitute for a registered person.

Information



How to get to HLRS by car

Leave autobahn A8 or A81 at the intersection „Autobahnkreuz Stuttgart“ in the direction of „Vaihingen“. Take exit „Universität“.

At the traffic light turn left into „Universitätsstraße“. Follow this road for about 2 km to Nobelstraße19. The HLRS is on the left side.

Parking facilities are available on the Nobelstraße or the site of IMS CHIPS.

To IMS CHIPS turn right into „Allmandring“ and then turn immediately left. IMS is the green building on the right, set back from the street. Parking spaces are available opposite to the entrance.

Organization

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IMS CHIPS

Partner for Advanced Nanopatterning



17th Workshop „Beams & More“
Thursday, November 14th, 2019

HLRS Höchstleistungsrechenzentrum Stuttgart
Nobelstraße 19, Stuttgart


Institut für Mikroelektronik Stuttgart

17th Workshop “Beams & More”

Dear colleagues,

I am honored to continue the “Beams & More” workshop initiated by Mathias Irmscher and it is a special pleasure for me to cordially invite you.

This one-day event is not only a well-established information platform on micro and nano patterning techniques and corresponding applications. It also provides best networking options by exploring new business opportunities enabled using technologies from IMS and partners.

I am proudly announcing 15 contributions from our collaborating partners as well as two IMS presentations on the following topics:

- Progress in EUV lithography
- Nanoimprint Lithography
- Laser-structuring
- Metrology
- Silicon Photonics
- Micro Optics
- MEMS

We recently updated our infrastructure significantly.

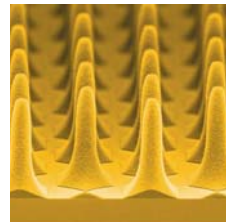
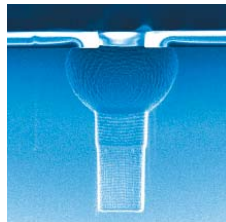
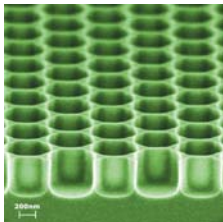
Our wet benches were upgraded to latest standards.

A new coater and developer for masks and wafers was installed and has been qualified.

Our highlight is a new key tool for MEMS, master and photonic devices, a wafer etch cluster equipped with four chambers. The different chambers are designed for wafer sizes up to 200mm and include metal etching, cryogenic silicon etching and the Bosch process. Installation is underway and we expect to have the cluster etch tool ready for operation in October 2019.

I am looking forward to the various presentations and to meet you personally at the workshop.

Sincerely
Julian Hartbaum



Program

Thursday, November 14th, 2019

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| Julian Hartbaum IMS CHIPS Stuttgart, Germany | Welcome and IMS CHIPS update 2019 | 9:30 |
| Lars Wischmeier Carl Zeiss SMT Oberkochen, Germany | Pushing limits of optical lithography: Status and future perspectives of EUVL optics | 9:50 |
| Eelco van Setten ASML Veldhoven, The Netherlands | Progress on 0.33 NA and High-NA EUV systems for High-Volume Manufacturing | 10:10 |
| Yuki Yamada Advantest Saitama, Japan | Novel CD-SEM technology for a shadow phenomenon in SEM image | 10:30 |
| Markus Waiblinger Carl Zeiss SMT Rossdorf, Germany | Electrons vs. defects - Fast or furios | 10:50 |
| Coffee Break | | 11:10 |
| Christof Klein IMS Nanofabrication Vienna, Austria | MBMW-201: The second generation multi-beam mask writer | 11:30 |
| Ulf Weidenmüller Vistec Electron Beam Jena, Germany | Vistec's Tool Box for Proximity Effect Correction | 11:50 |
| Markus Greul IMS CHIPS Stuttgart, Germany | Software based Linearity and Resolution Improvements for HIMT VPG400 Laser Write | 12:10 |
| Anja Voigt micro resist technology Berlin, Germany | Tailor-made material solutions for advanced 3 D micro and nano patterning processes | 12:30 |
| Matthias Schirmer Allresist Strausberg, Germany | e-beam application with Medusa 82 and other new resists developments | 12:50 |
| Lunch Break | | 13:10 |

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| Jonas Khan EVGroup St. Florian am Inn, Austria | Nanoimprint Lithography – Transition to 300 mm Volume Manufacturing | 14:20 |
| Jatinder Kaur kdg opticomp GmbH Elbigenalp, Austria | Injection moulded diffraction gratings on curved surfaces | 14:40 |
| Markus Sauer Swarovski Wattens, Austria | Imprinting Brilliance – what it takes to make NIL sparkle | 15:00 |
| Meik Panitz Jenoptik Optical Systems Dresden, Germany | Membrane Fabrication for Sensor Applications | 15:20 |
| Coffee Break | | 15:40 |
| Daniel Flamm TRUMPF Laser- und Systemtechnik Ditzingen, Germany | Structured light concepts for ultrafast materials processing | 16:00 |
| J. Hatzigeorgopoulos, Rémi Bourgois Safran Reosc Saint-Pierre-du-Perray, France | ELT Optics Manufacturing – Year 2 Report & metrology means | 16:20 |
| Florian Sotier InnoLas Photonics Krailing, Germany | Microstructuring with Femtosecond Lasers | 16:40 |
| Mathias Kaschel IMS CHIPS Stuttgart, Germany | Silicon Photonics: Current projects at IMS CHIPS | 17:00 |
| Joint Dinner at relexa Waldhotel Schatten | | 18:30 |